

# Jan Doise

## List of Publications by Year in descending order

Source: <https://exaly.com/author-pdf/7056350/publications.pdf>

Version: 2024-02-01

19  
papers

161  
citations

1684188

5  
h-index

1199594

12  
g-index

19  
all docs

19  
docs citations

19  
times ranked

236  
citing authors

#	ARTICLE	IF	CITATIONS
1	Sub-5 nm Patterning by Directed Self-Assembly of Oligo(Dimethylsiloxane) Liquid Crystal Thin Films. <i>Advanced Materials</i> , 2016, 28, 10068-10072.	21.0	64
2	Implementation of templated DSA for via layer patterning at the 7nm node. , 2015, , .		17
3	Implementation of surface energy modification in graphoepitaxy directed self-assembly for hole multiplication. <i>Journal of Vacuum Science and Technology B:Nanotechnology and Microelectronics</i> , 2015, 33, 06F301.	1.2	13
4	Strategies for Increasing the Rate of Defect Annihilation in the Directed Self-Assembly of High- $\chi$ Block Copolymers. <i>ACS Applied Materials &amp; Interfaces</i> , 2019, 11, 48419-48427.	8.0	11
5	Influence of template fill in graphoepitaxy directed self-assembly. <i>Journal of Micro/ Nanolithography, MEMS, and MOEMS</i> , 2016, 15, 031603.	0.9	9
6	Contact hole multiplication using grapho-epitaxy directed self-assembly: process choices, template optimization, and placement accuracy. <i>Proceedings of SPIE</i> , 2014, , .	0.8	7
7	Process optimization of templated DSA flows. , 2014, , .		6
8	EUV patterned templates with grapho-epitaxy DSA at the N5/N7 logic nodes. <i>Proceedings of SPIE</i> , 2016, , .	0.8	5
9	Via patterning in the 7-nm node using immersion lithography and graphoepitaxy directed self-assembly. <i>Journal of Micro/ Nanolithography, MEMS, and MOEMS</i> , 2017, 16, 023506.	0.9	5
10	Dual brush process for selective surface modification in graphoepitaxy directed self-assembly. , 2017, , .		4
11	DSA graphoepitaxy calibrations for contact hole multiplication. <i>Proceedings of SPIE</i> , 2015, , .	0.8	3
12	Integration of a templated directed self-assembly-based hole shrink in a short loop via chain. <i>Journal of Micro/ Nanolithography, MEMS, and MOEMS</i> , 2016, 15, 043505.	0.9	3
13	Influence of Homopolymer Addition in Templated Assembly of Cylindrical Block Copolymers. <i>ACS Nano</i> , 2019, 13, 4073-4082.	14.6	3
14	Influence of template fill in graphoepitaxy DSA. , 2016, , .		2
15	High- $\chi$ , Si-Containing Block Copolymers and Process Strategies for Directing Their Self-Assembly. <i>Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi]</i> , 2017, 30, 187-190.	0.3	2
16	Impact of annealing temperature on DSA process: toward faster assembly kinetics (Conference) Tj ETQq0 0 0 rgBT /Overlock <sub>2</sub> Tf 50 1		2
17	Defect mitigation in sub-20nm patterning with high-chi, silicon-containing block copolymers. , 2019, , .		2
18	Dual brush process for selective surface modification in graphoepitaxy directed self-assembly. <i>Journal of Micro/ Nanolithography, MEMS, and MOEMS</i> , 2017, 16, 1.	0.9	2

#	ARTICLE	IF	CITATIONS
19	Studying the effects of chemistry and geometry on DSA hole-shrink process in three dimensions. , 2018, , ·		1